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LIST OF PRIOR ART CITED BY APPLICANT(S)
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Applicant(s)
J. Thiele et al.
File Date : 6/4/01
Group : 2651

U.S. PATENT DOCUMENTS

Exam. Intl.	Document Number	Date	Name	Class/ Subclass	Filing Date
<i>92</i>	A1	5,025,430	06/18/91	Takokoro et al.	G11B 13/04 03/31/88
<i>92</i>	A2	5,530,685	06/25/96	Katayama et al.	G11B 11/00 10/28/94
<i>92</i>	A3	5,625,617	04/29/97	Hopkins et al.	G11B 7/00 09/06/95
<i>92</i>	A4	5,889,641	03/30/99	Belser et al.	G11B 5/127 05/05/97
<i>92</i>	A5	5,986,978	11/16/99	Rottmayer et al.	G11B 11/00 01/12/98
	A6	6,130,779	10/10/00	Carlson et al.	G02B 5/18 07/06/98
	A7				
	A8				
	A9				

FOREIGN COUNTRIES

	Document Number	Date	Country	Class/ Subclass	Translation YES NO
	B1				
	B2				
	B3				
	B4				
	B5				
	B6				
	B7				
	B8				
	B9				

OTHER PRIOR ART (INCLUDE AUTHOR, TITLE, DATE, PERTINENT PAGE, ETC.)

<i>92</i>	C1	A. Partovi et al., High -Power Laser Light For Near-Field Optics and Its Application to High-Density Optical Data Storage, 09/13/99, Volume 75, Number 11, pages 1515-1517.			
<i>92</i>	C2	A. Partov, Optical Near-Field Aperture Storage Technique(ONFAST) For High Density, High Performance Storage Applications, 07/99, SPIE Vol. 3864, pages 352-354.			
<i>92</i>	C3	D. Weller et al., High Ku Materials Approach to 100 Gbit/In ² , 07/09/99, pages 1-6.			
	C4				
	C5				

EXAMINER

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*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant(s).